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said raster element of said first mirror or lens is imaged in said reticule plane by said raster element of said second mirror or lens;

an image of said raster element of said first mirror or lens is partially superimposed in said reticule plane; and

said secondary light source is imaged in an exit pupil by said optical element.

53  
104. Process for the production of microelectronic components according to claim ~~53~~ 11

11  
105. The illumination system according to claim ~~62~~ 10, wherein said light source is a plasma focus source.

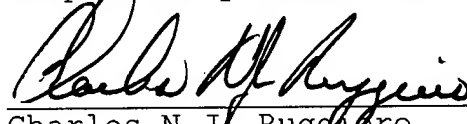
13  
106. The illumination system according to claim ~~63~~ 12, wherein said light source is a pinch-plasma source.

#### REMARKS

New claims 53 through 106 are added to properly protect the full scope of the invention.

Respectfully submitted,

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